

Electronic supplementary information

for

Highly ordered TiO₂ nanostructures by sequential vapour infiltration of block copolymer micellar films in an atomic layer deposition reactor†

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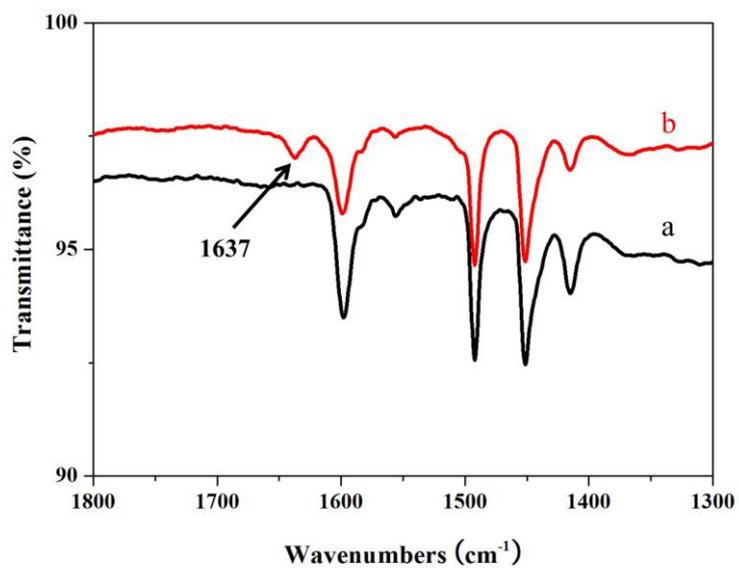


Figure S1. FTIR spectra of PS_{23k}-*b*-P4VP_{4.5k} films before (a) and after (b) exposure of TiCl₄ vapour in the ALD reactor.